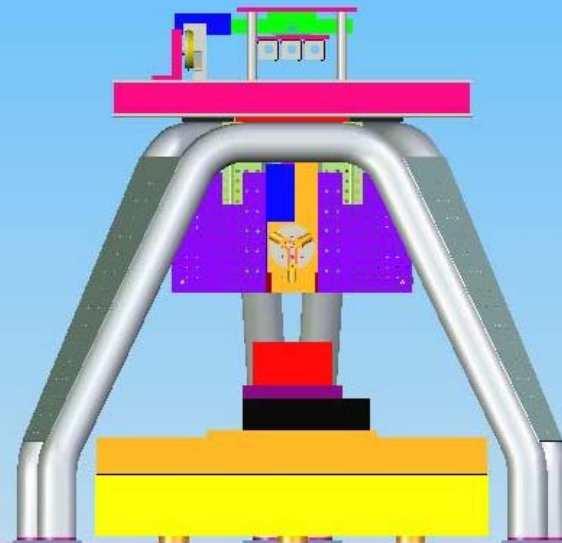


Laser Microengineering and the Advances that can be Gained by Using the Jefferson Laboratory Free Electron Laser

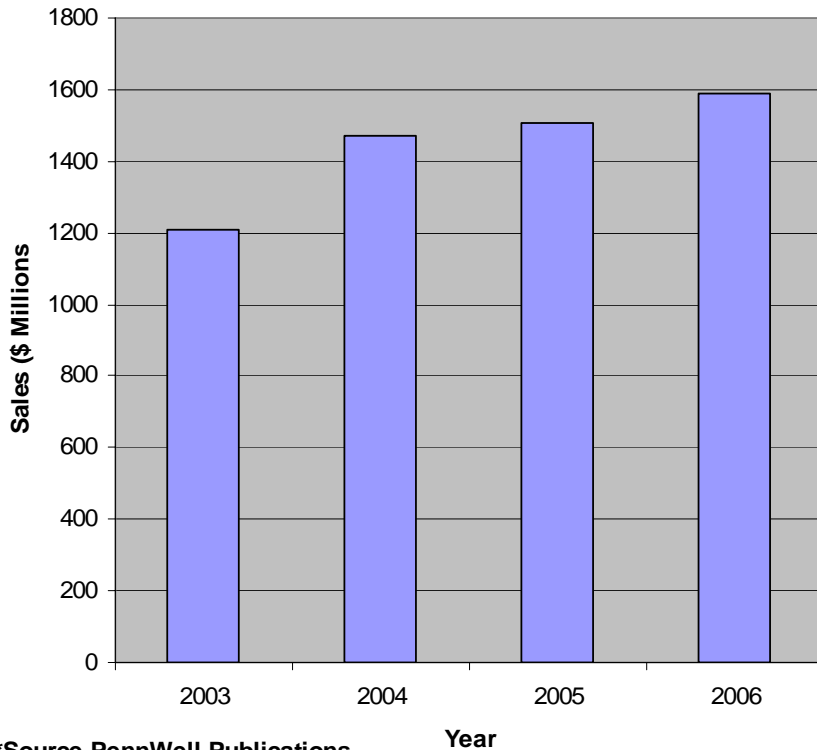
Henry Helvajian
The Aerospace Corporation
Los Angeles, California

**The Laser Microengineering
Experimental Station”
at the
Jefferson Laboratory Free Electron
Laser Facility**



**Enable Development of Laser Materials Processing Technology
in the USA**

Worldwide nondiode-Laser Sales for Materials Processing Applications*

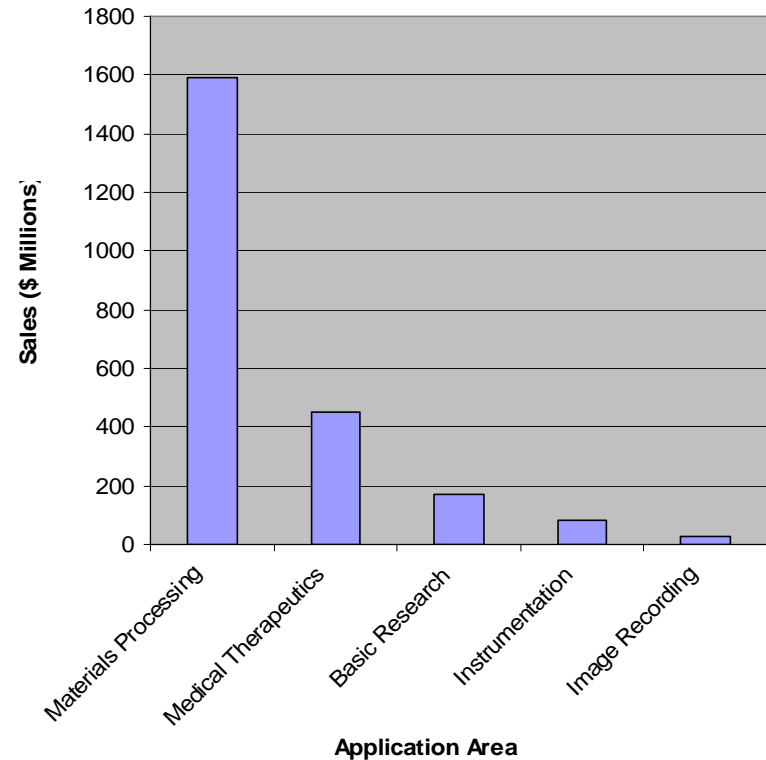


*Source PennWell Publications

**~ 1.6 \$B in Laser Sales
Alone Expected in 2006**

Materials Processing Applications Lead World Wide Sales

Worldwide nondiode-Laser Sales by Application in 2006*



*Source PennWell
Publications

Laser Microengineering

Controlled Alteration of a Material Property in the Surface or Volume that with Patterning Leads to the Development of a Structure/Device/Component

Examples of Processes

- **Single laser volumetric exposure in photoactive materials (e.g. holography).**
- **Multi laser volumetric exposure in active materials (e.g. photonic crystals).**
- **Percussion and ablative machining**
- **Polishing (e.g. mirrors coatings)**
- **Laser chemical vapor deposition (LCVD)**
- **Laser induced plasma deposition**
- **Laser induced forward transfer (LIFT)**
- **Laser induced phase transformation (i.e. crystallization, amorphous)**
- **Fusing (i.e. welding on the micron scale)**
- **Bending (i.e. curvature control on the nanometer scale)**
- **Texturing (i.e. control of surface topology)**
- **Pulsed laser desorption (atoms/molecules) and ablation (monolayers or greater).**

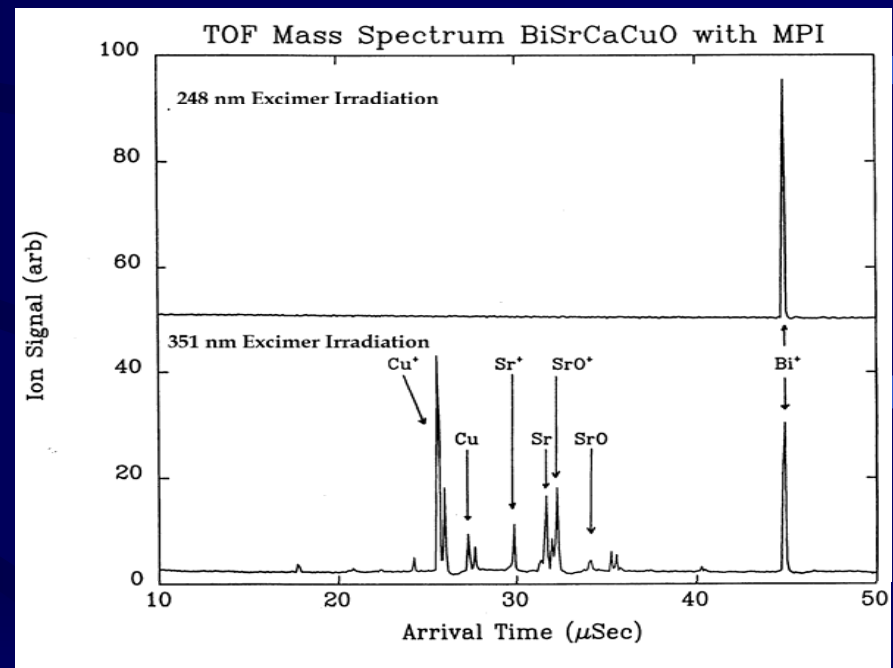
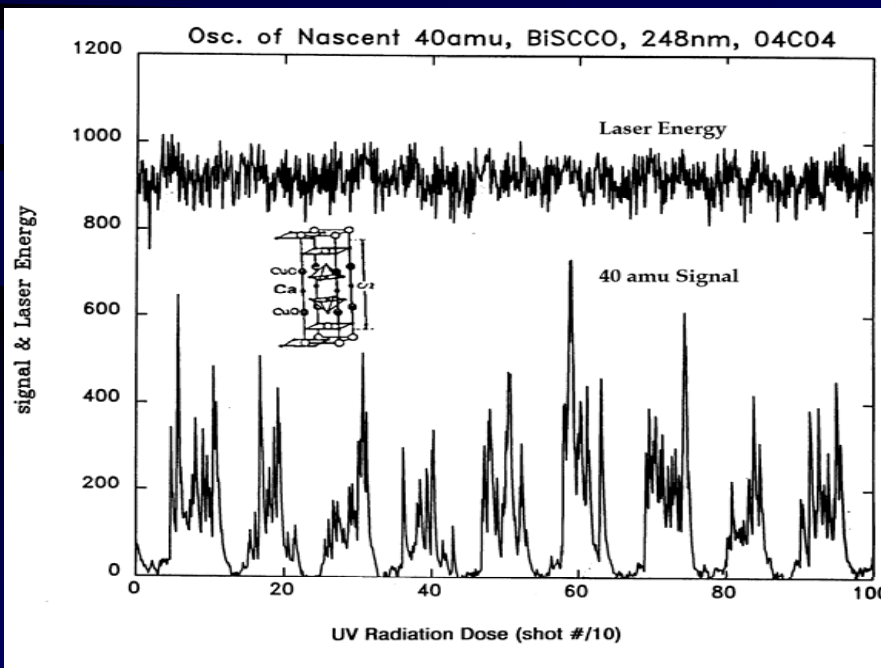
“Rules of thumb” for Laser Microengineering

- In inducing a physical process by laser irradiation, there is more control with multiple small-energy laser pulses rather than a single large-energy pulse.
- Laser material interaction processes that are mostly driven by non-thermal events are likely to be more precise than processes governed by thermal induced phenomena.
- Tuning to a laser material interaction resonance helps.

Examples From Prior Experiments

“atomic layer-by-layer peeling & species specific desorption”*

- Low-KE Pulsed Atomic Beam Source for Controlling Epitaxial Deposition.
 - Practical applications
 - Atomic beam of specific species “layer-by-layer” atomic peeling of surfaces.
 - Impracticality
 - Measured removal rates $10^{-7} - 10^{-2}$ monolayers/shot (10^{11} species/cm² per shot).
 - Scaling
 - At MHz laser repetition rate deposition rates can be made to compete with MBE (deposition rates 0.1ML/s⁻¹).

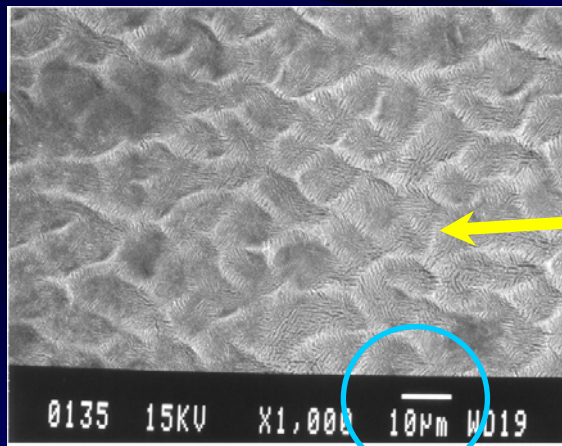


Examples From Prior Experiments

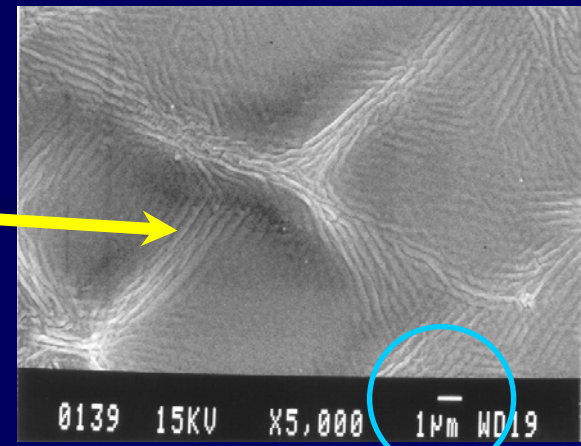
“surface texturing in the non-thermal domain”*

- Laser induced surface texturing in the “non thermal domain”.
 - Practical Applications
 - Fabrication of a catalytically active surface on metals.
 - Nanometers scale control surface topological features
 - Scaling
 - 1 KHz laser can prepare surface at speeds ~ 0.005 mm/sec
 - 1 MHz laser can prepare surface at speeds ~ 5 mm/sec.

15K Laser Shots (355nm)
Low Fluence ($<30\text{mJ/cm}^2$)



200K Laser
Shots (355nm)
Low Fluence
($<30\text{mJ/cm}^2$)



- Practicalities of Industry
 - Utilizing large number of laser pulses per unit area means increased processing time and therefore increased cost.
 - Advantages of processing material in the “non-thermal regime” are nullified because of the large number of required laser pulses. These processes become relegated as scientific observation and deemed not practical.
- Possible “game” or paradigm changers
 - A laser with high repetition rate ($>$ MHz) and high average power that is wavelength tunable.
 - A means for controllably delivering, with high fidelity, laser pulses with prescribed amplitudes (energy) to a material that is moving under pattern control.
 - A laser material process in which the laser light only “activates” the material but the desired physical transformation occurs in a follow-on batch process (e.g. chemical etch step)

The JLAB IRFEL & UVFEL

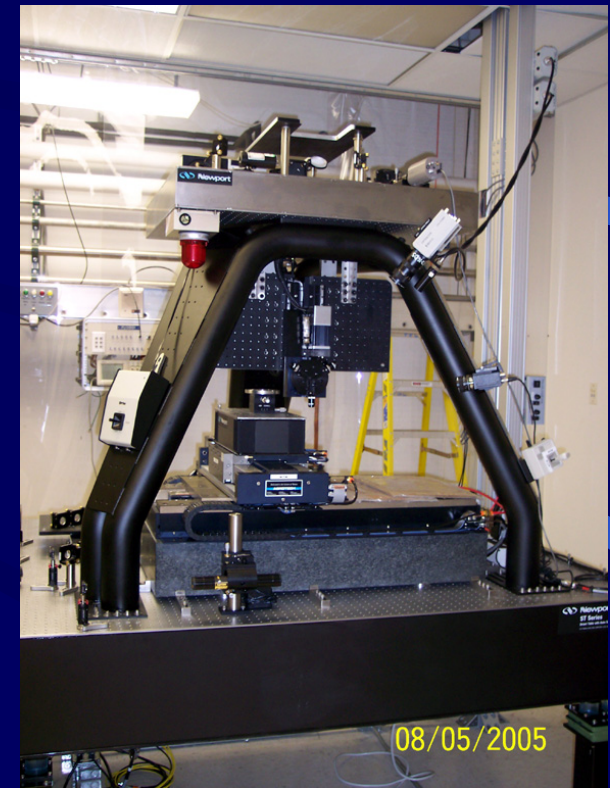
Unique Light Sources for Laser Material Processing

High Repetition Rate - Tunability



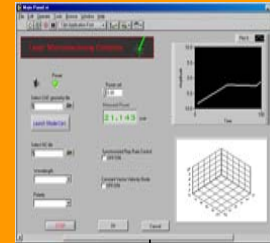
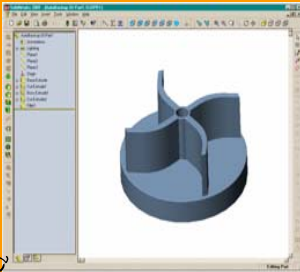
The Laser Microengineering Experimental Station (LMES) at JLAB

A Three Axes Motion Tool Designed For the
Controlled Delivery of the FEL Light
to a Moving Surface (speeds $> 400\text{mm/sec}$)
with
Positioning Accuracy on the Nanometer Scale
and
Illumination Spot Size that can be Dialed
Down to Micrometer Scale



Useful Attributes of the LMES

User Capabilities Microengineering & Rapid Prototyping Software Module Sequences



Automated
RUN JOB

Start

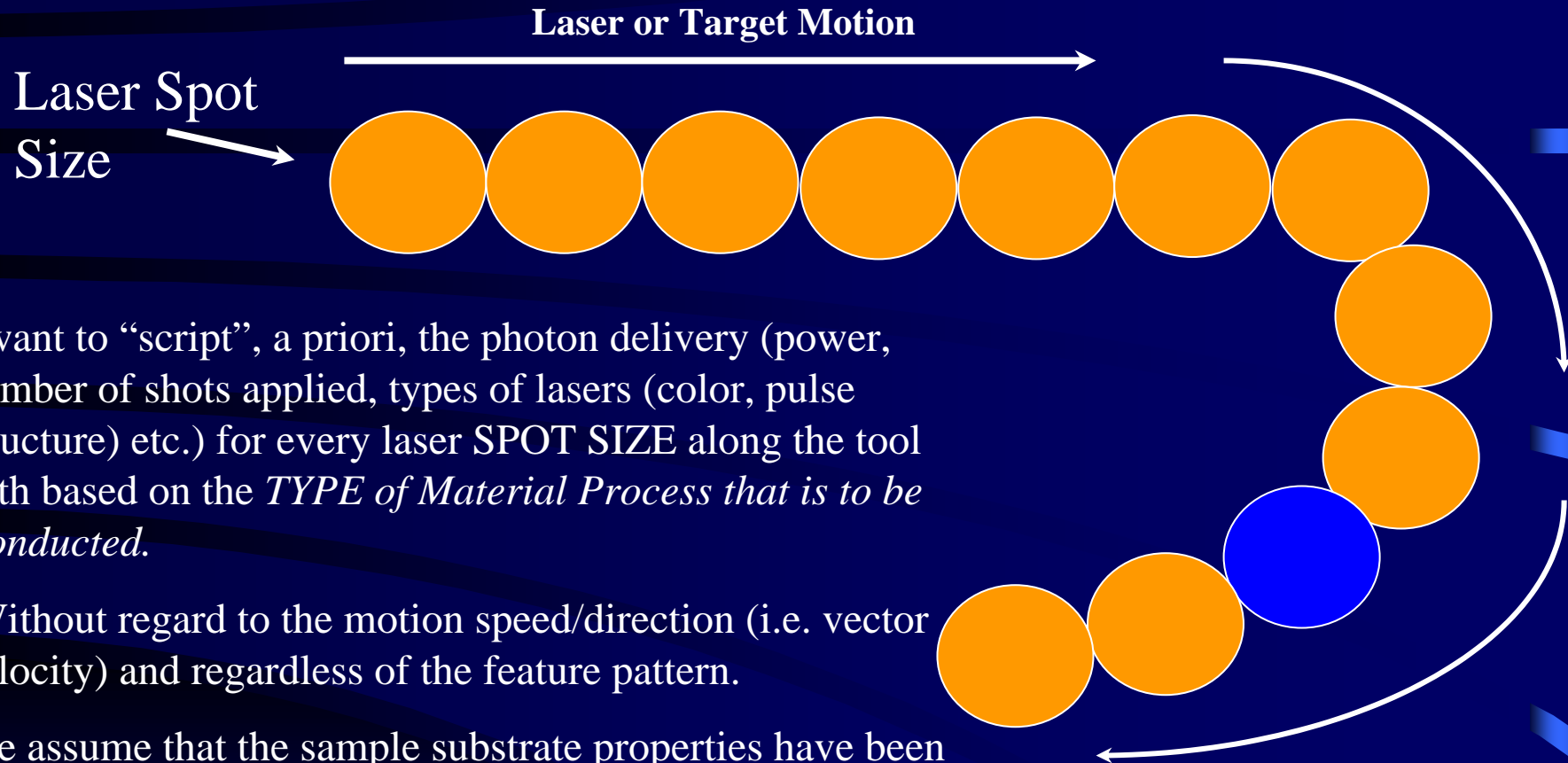
The collage includes several software interfaces:

- Acrobat Reader - [V9M663.pdf]**: A document viewer showing a PDF with technical text and diagrams.
- Mastercam**: A CAD/CAM software interface with multiple windows showing 3D models and toolpaths. Text overlays include:
 - "High-speed facing"
 - "Smooth, automated circle milling"
 - "Full 'trochoidal' cutting prevents tool burial"
 - "Specialized high-speed pocketing"
- Automation 3200**: A control panel with various input fields and buttons.
- Run Page (Page 1)**: A window displaying numerical data and status indicators.
- High Intelligent 32 Axis Motion, Vision & I/O System**: A window showing a 3D wireframe model of a mechanical part.

AUTOMATION 3200 THE INTELLIGENT 32 AXIS
MOTION, VISION & I/O SYSTEM

Dynamic Control of Laser Power to Compensate for the Expected Changes in Motion Velocity that Occurs During Patterning

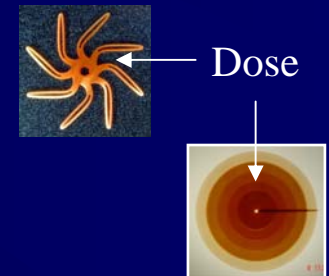
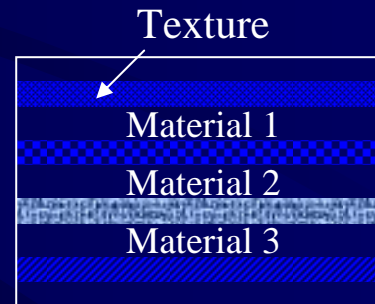
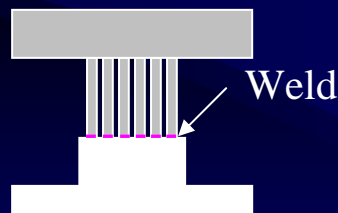
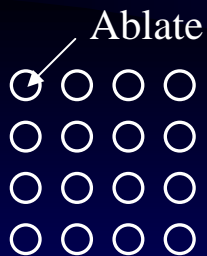
High Fidelity Control of Laser Pulse Energy to “target”



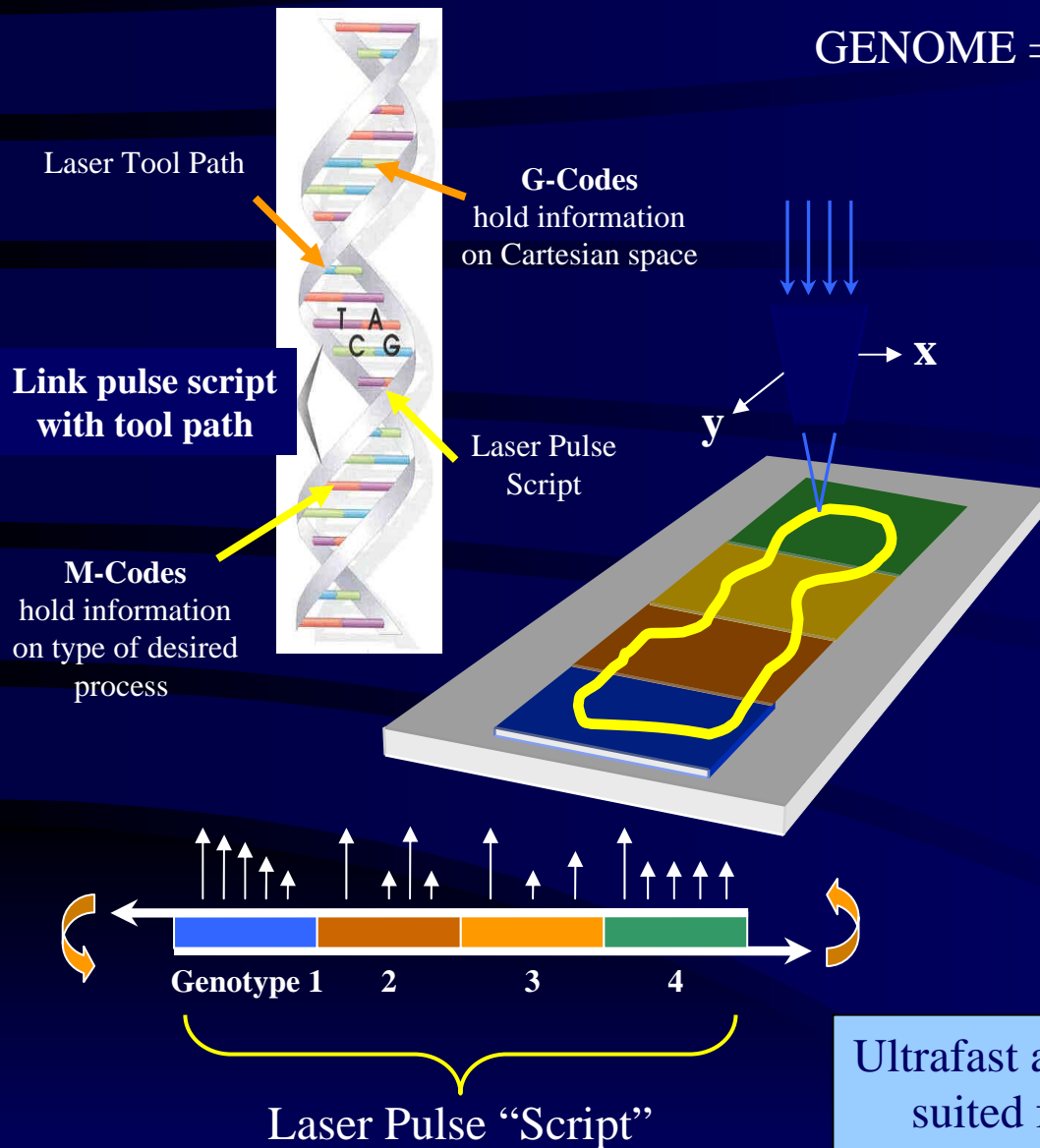
- I want to “script”, a priori, the photon delivery (power, number of shots applied, types of lasers (color, pulse structure) etc.) for every laser SPOT SIZE along the tool path based on the *TYPE of Material Process that is to be Conducted*.
- Without regard to the motion speed/direction (i.e. vector velocity) and regardless of the feature pattern.
- We assume that the sample substrate properties have been mapped in 3D, a priori.
- We assume that the material has “properties” that can be expressed via controlled deposition of light.

Laser Material Processing Using Modulated Pulse Sequences

Process	Laser Pulse Structure Mat1	Laser Pulse Structure Mat2
a) Ablation		
b) Welding		
c) Texturing		
d) Dosing		



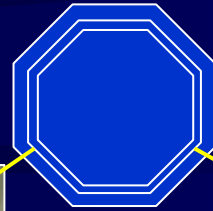
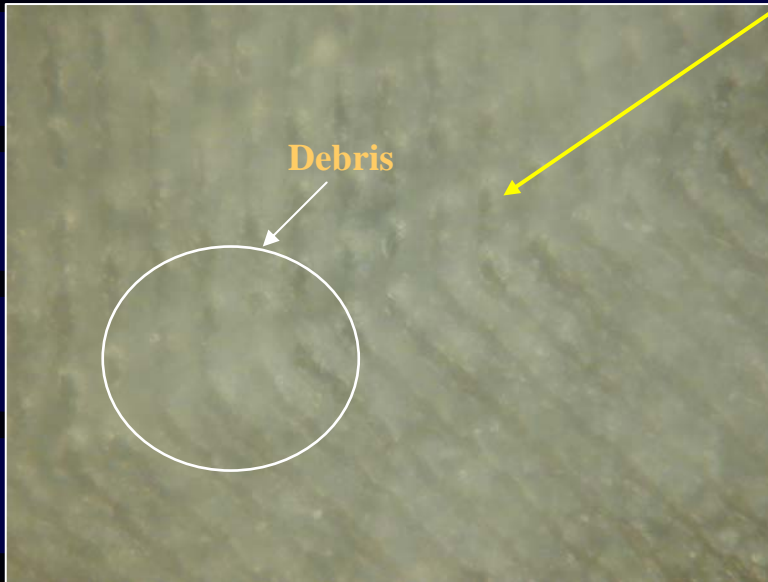
Use of Digitally-Scripted Genotype Pulse Patterns



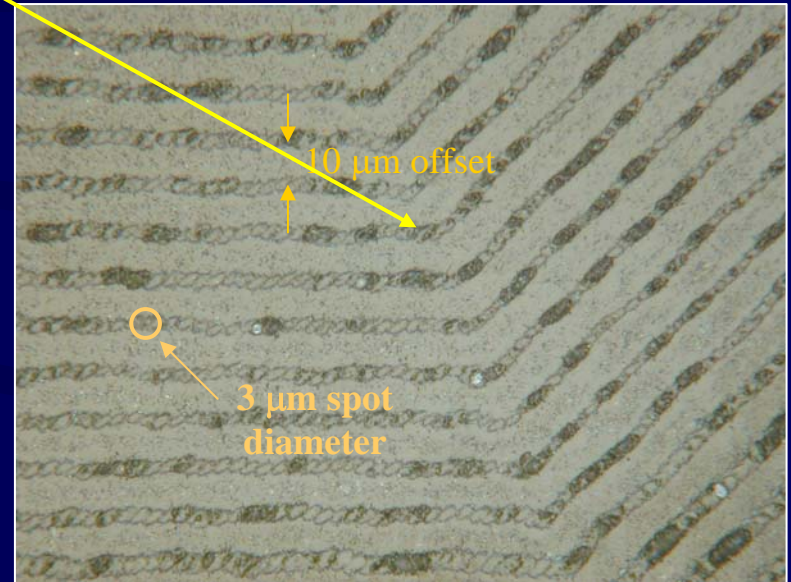
Ultrafast and high repetition rate lasers are ideally suited for digitally-scripted laser processing

Ablation of Glass Using Modulated fs Laser Pulses at 400 nm

Velocity Compensation OFF



Velocity Compensation ON

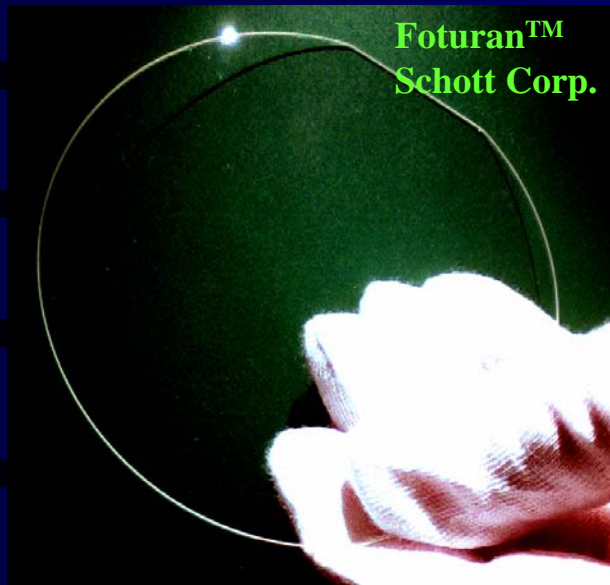


- Spallation and debris formation
- Fractures and thermal-induced stress

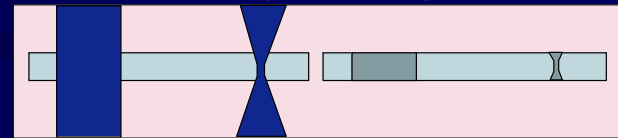
- Localized material removal
- Patterns are clean and well defined

Processing Photoceramic Glasses

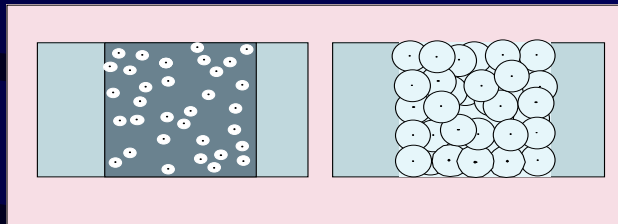
Typical Process Flow



Step 1: UV Illumination/Latent Image

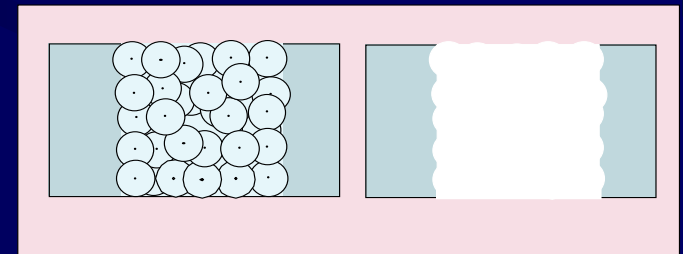


Step 2: Ceramization to a Meta-Silicate

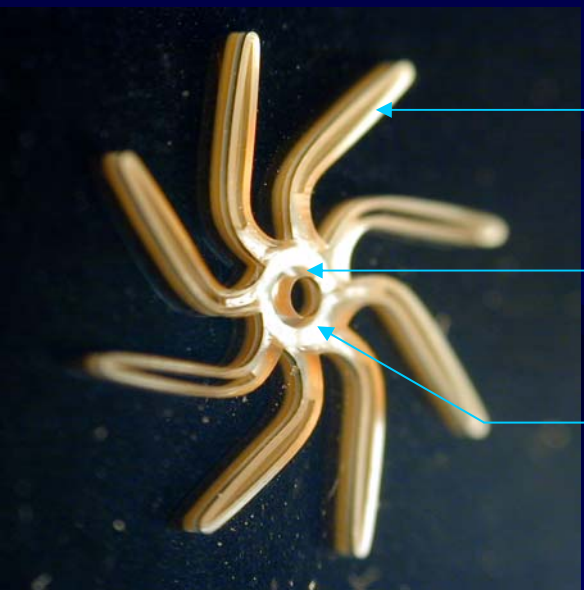
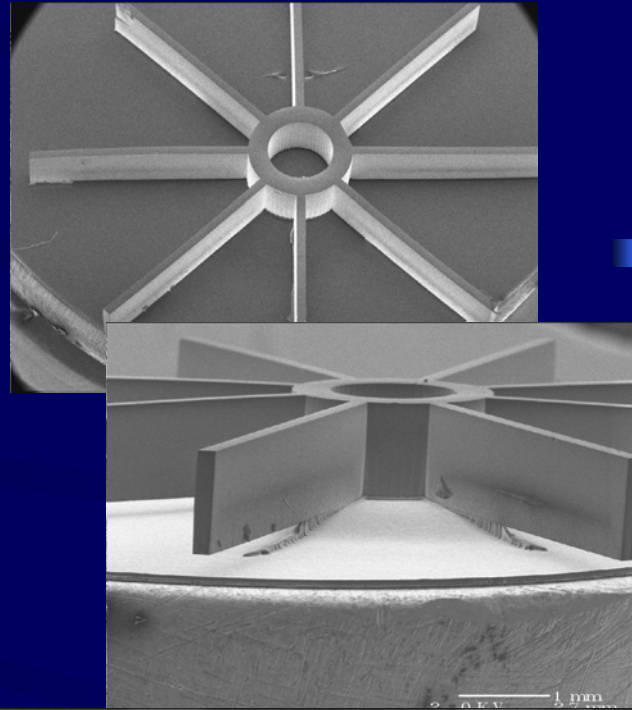
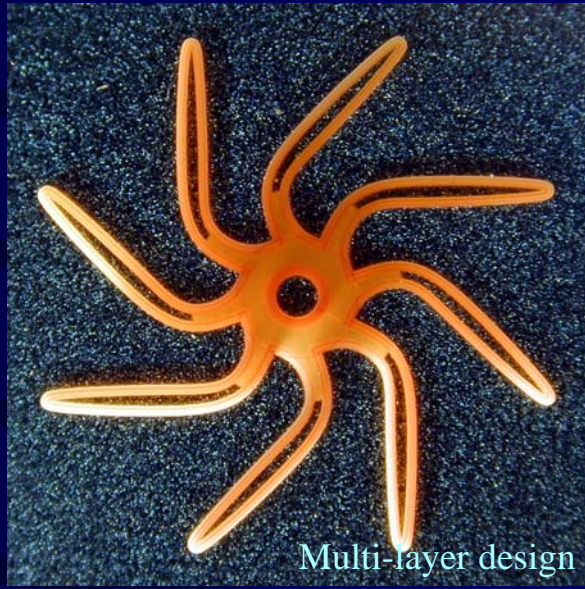


Step 3: Preferential Isotropic Etching

- Crystalline Li_2SiO_3 dissolves 20x faster than the amorphous glass in 5% hydrofluoric acid.
- $\text{Li}_2\text{SiO}_3 + 3\text{HF} \rightarrow 2\text{LiF} + \text{H}_2\text{SiF}_6 + 3 \text{H}_2\text{O}$



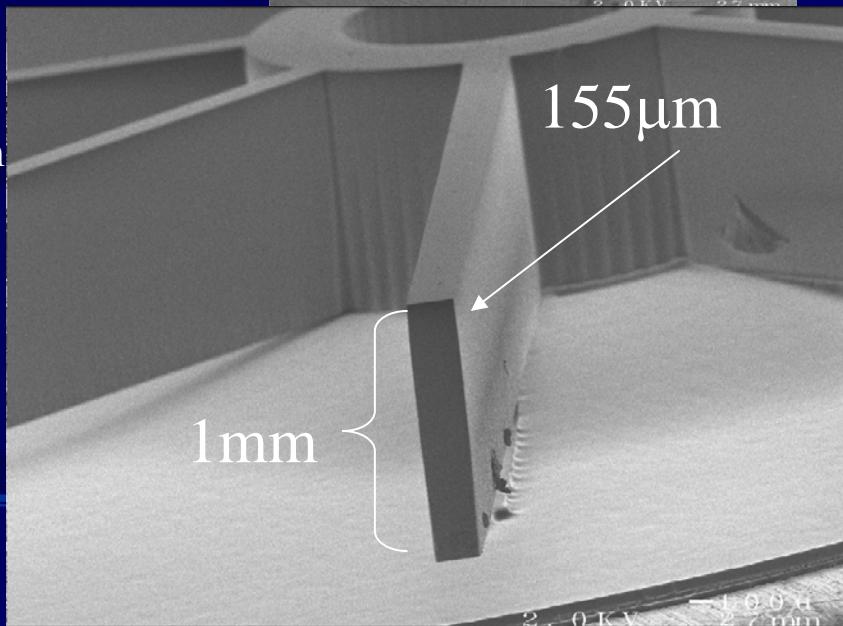
Arrays of Meso-scale Microturbines



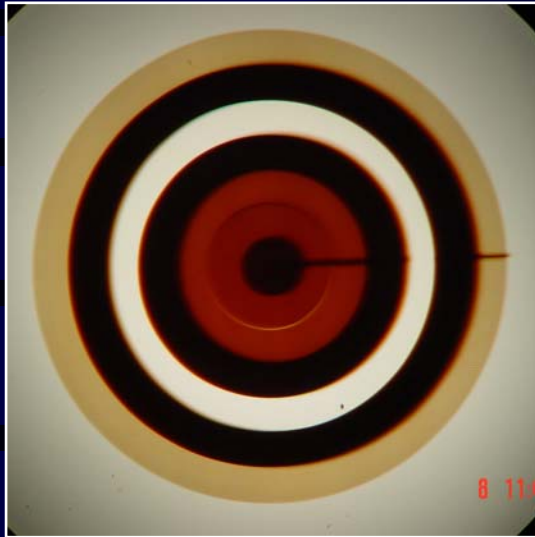
Rotors: 200 μm thick

Spindle depth: 500 μm

Trough: 300 μm

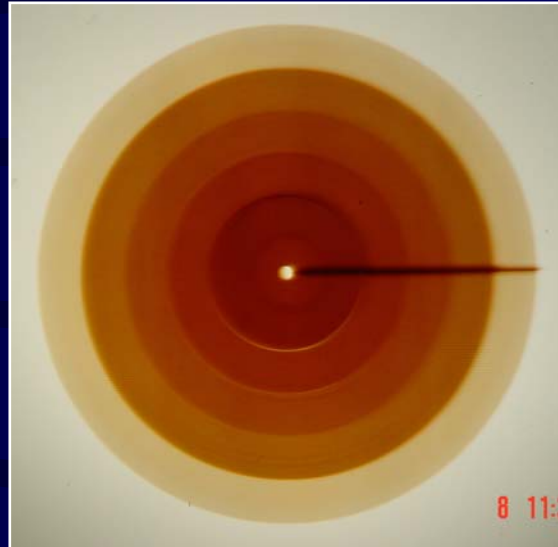


Exposed and baked



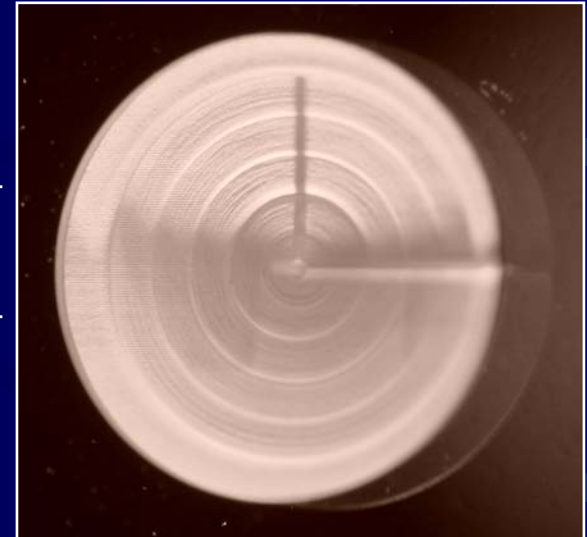
The Aerospace Corporation

Control of Optical Transmission (IR)



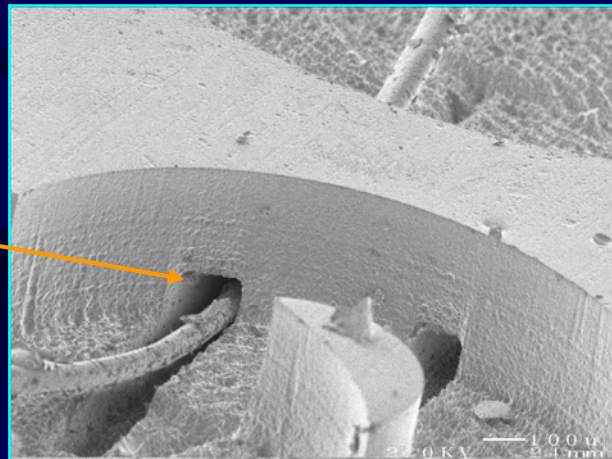
The Aerospace Corporation

**What time is it?
THz Fresnel Lens**



The Aerospace Corporation

Undercut Structures



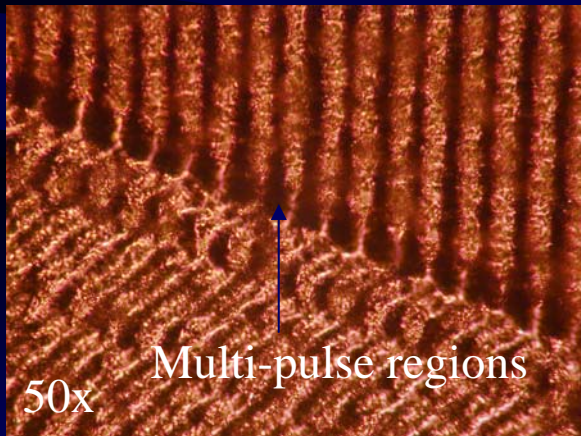
The Aerospace Corporation

Exposure of Photosensitive Glass Using Modulated fs Laser Pulses at 400 nm

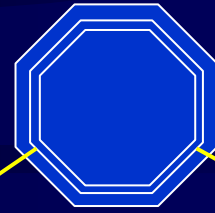
Velocity Compensation OFF



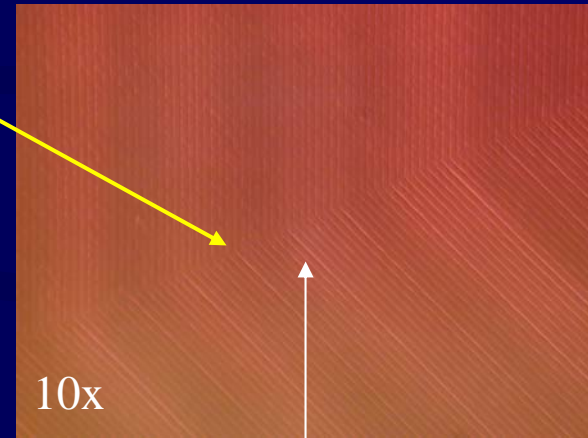
Over-exposure



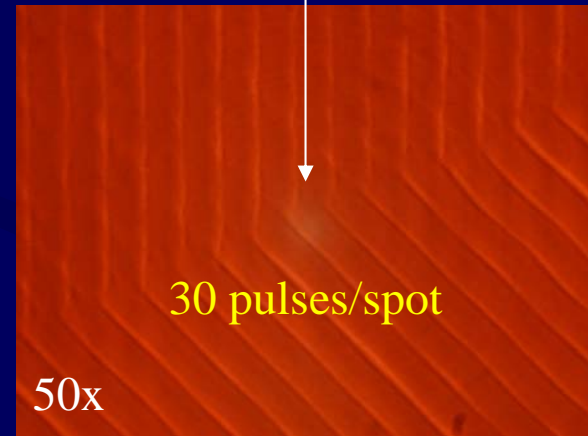
Multi-pulse regions



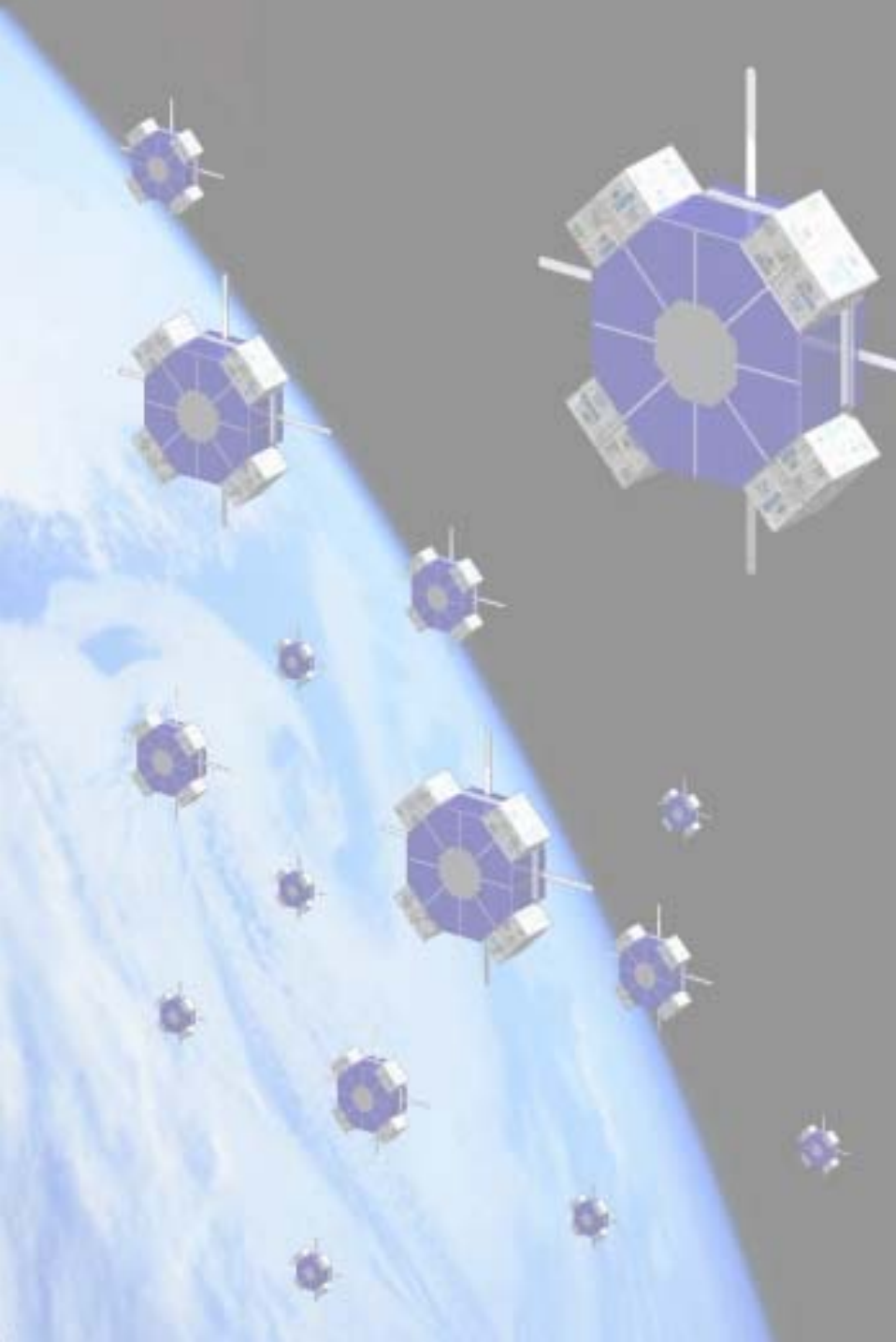
Velocity Compensation ON



Uniform exposure



**Why is the The Aerospace Corporation,
a Federally Funded Research & Development Center of
Department of Defense
Interested in the Development of a LMES?**



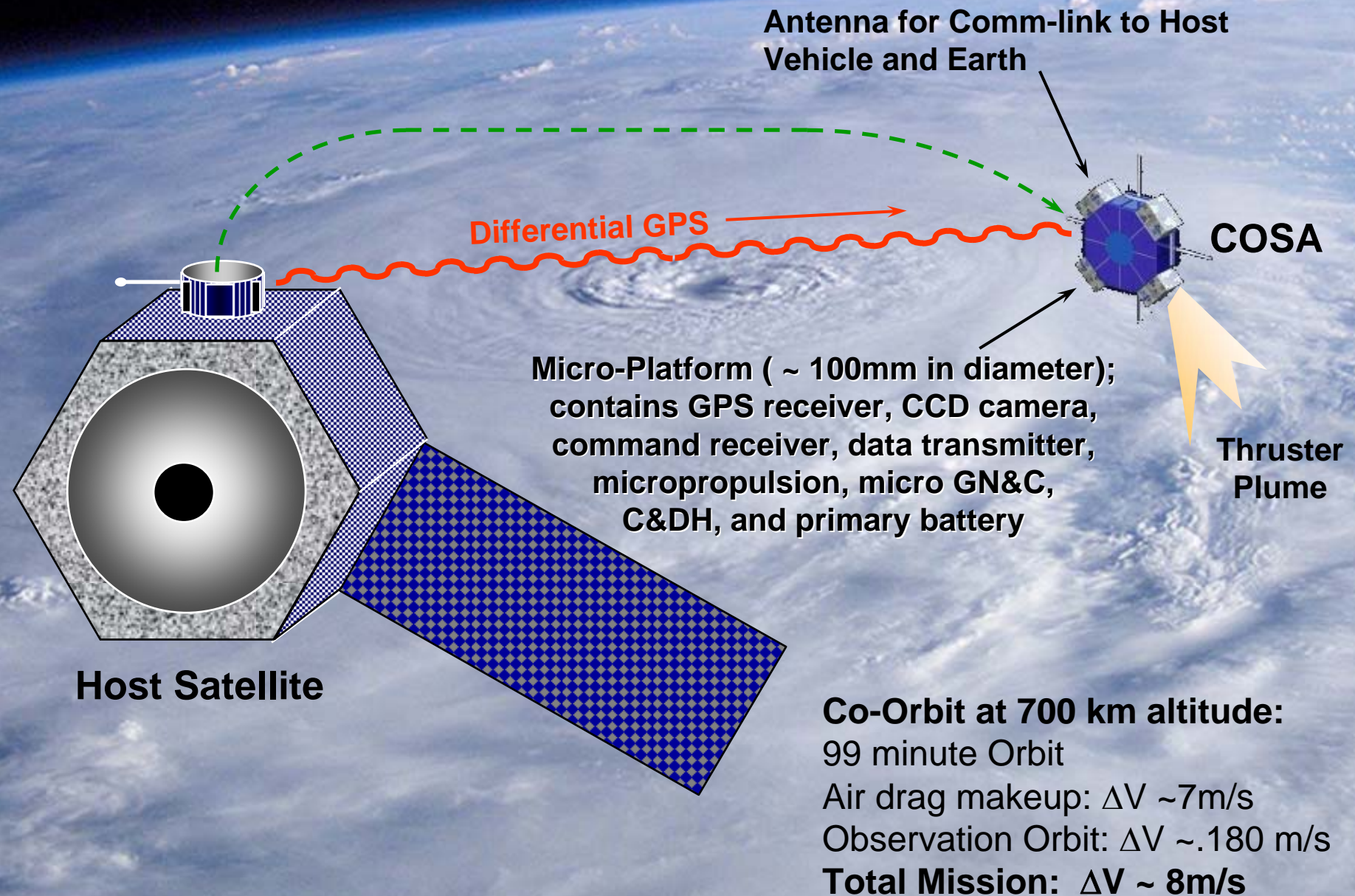
Development of a Direct-Digital Manufacturing Methodology for the Design, Fabrication and Assembly of Small Satellites

Satellites that are Mass Producible and can be Mass-Customized

Key: Materials in Satellite Must Serve a Multifunctional Role

Consider Glass-Ceramic Materials as Structural Support For Small Satellites

The Co-Orbiting Satellite Assistant (COSA) Mission



COSA Observation Trajectories

Co-orbital with Inclination:

Phasing orbit:

- 1st impulse: 3 mm/s
- 2nd impulse: 3 mm/s
- 99 minutes @ 700 km
- mN thrust levels

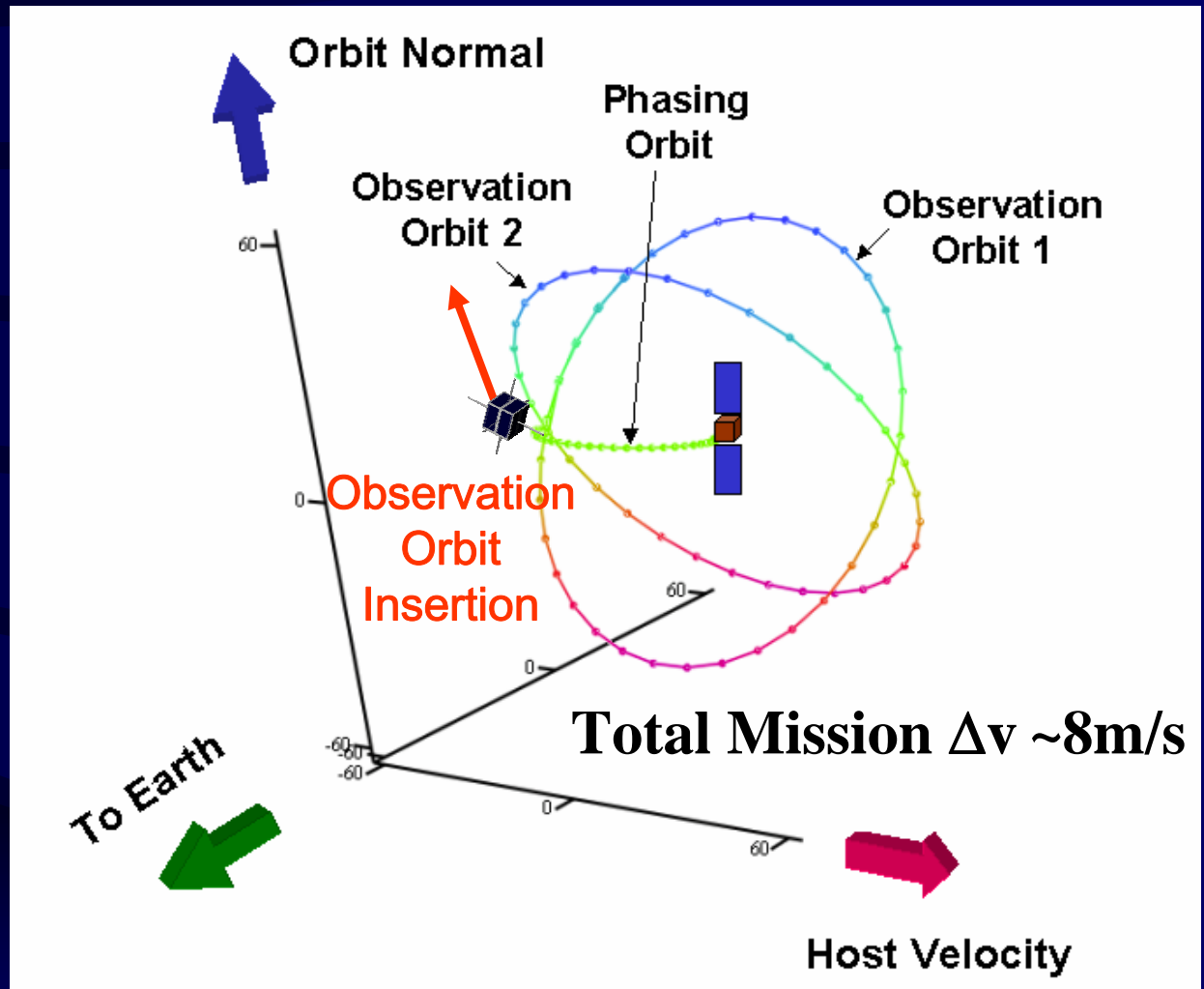
Observation orbits:

- Total: ~.180 m/s
- mN thrust levels

$$F\delta t = m \Delta v$$

$$\Delta v = 1\text{mN}(1\text{s})/0.1\text{Kg}$$

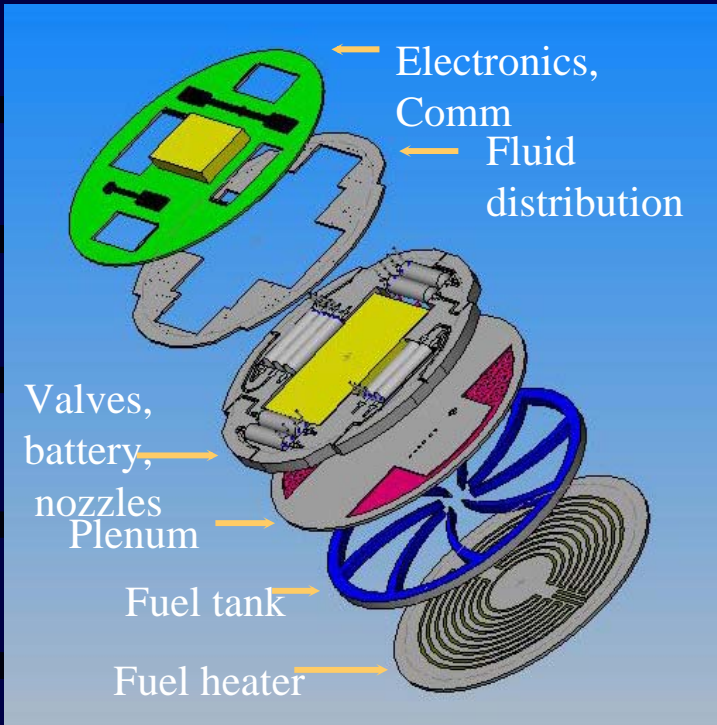
$$\Delta v = 0.01\text{m/sec}$$



Air Drag $\Delta v \sim 7\text{m/s}$

De-Orbit $\Delta v \sim 0.2\text{m/s}$

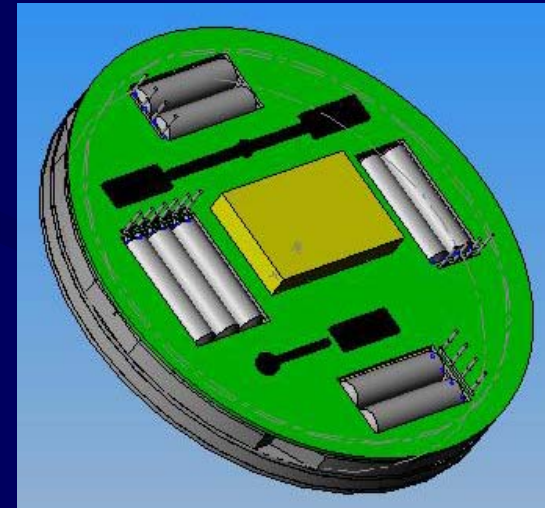
COSA: All Direct-Digital-Manufacturing



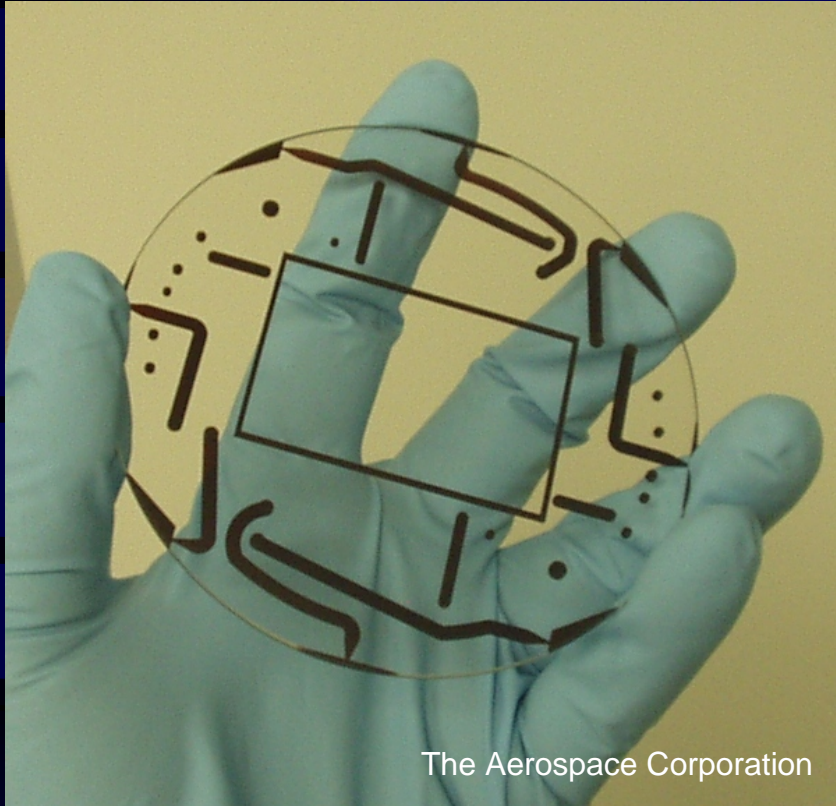
Manufacturing Approach:

- Generate solid models of all patterned PSGC wafers and components.
 - Conduct tests for form fit,
 - Conduct mission analysis tests.
- Generate tool-path files for all laser direct-write operations.
 - Material to be removed, deposited, altered.
- Translate tool-path code to patterning motion.
- Pattern via laser direct-write variable exposure processing

A Propulsion System with Guidance, Navigation and Control (GNC) in PSGC Material

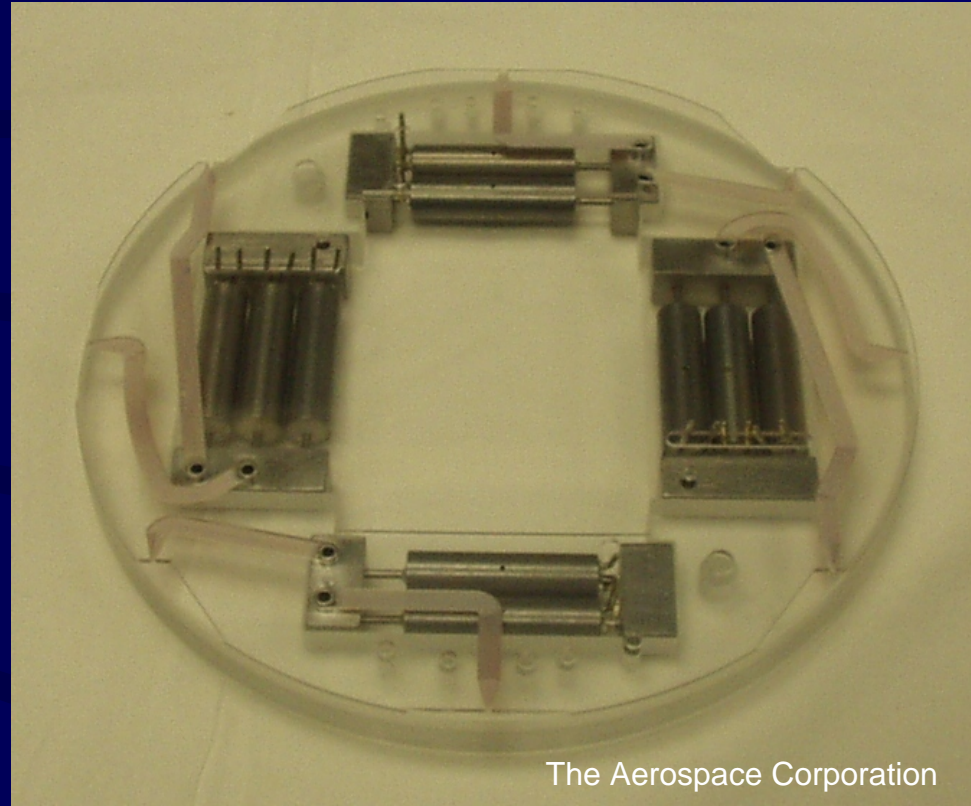


COSA Wafers



The Aerospace Corporation

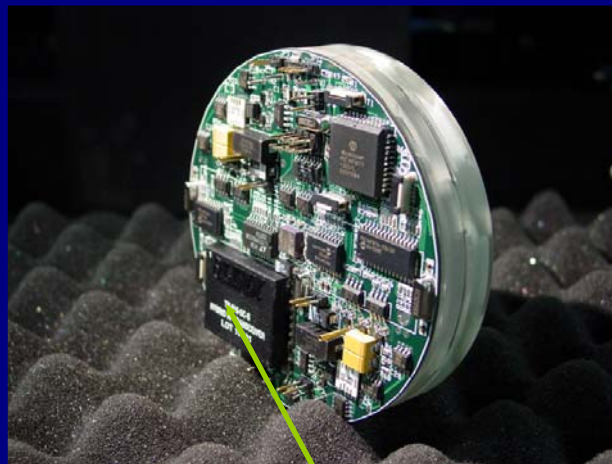
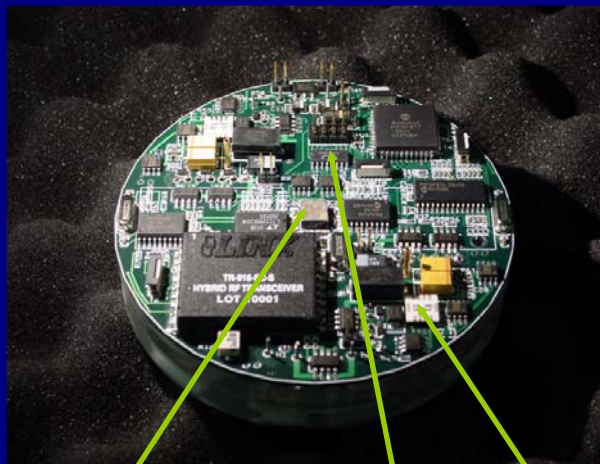
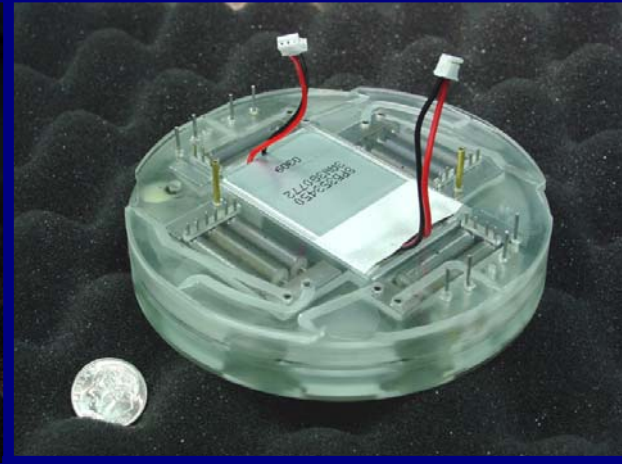
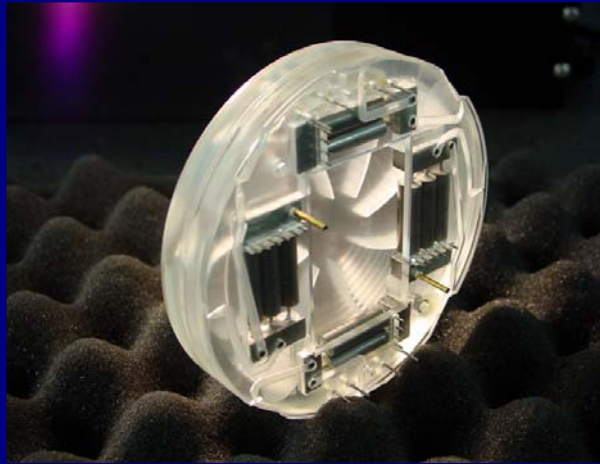
Exposed and baked nozzle layer



The Aerospace Corporation

Etched nozzle and valve layers with valves

“COXA: The Prototype Propulsion Module”*



MEMS GYRO

Pressure Sensor (x2)

Magnetometer

Wireless Telemetry

Orientation Control Tests for the COSA Vehicle “Hope”

Rotation on Air Table Without Thrust or Orientation Control



IMU guided Rotational Control with pulsed thrusting



COSA Manufacturing Process: Prototype Vehicle

COSA Process Time (hrs.)				
	Patterning	Baking	Polishing	Etching
Is Process Automated? Can it Run 24/7	Yes	yes	yes	yes
Wafer				
Heater	10	4	12	2
Fuel	0.25	0	0	0
Plenum	19	4	12	3
Spacer	2	4	12	1
Battery	0.25	0	0	0
Nozzle	17	4	12	3
Capping	7	4	12	1
SUM	55.5	20	60	10
Total Time to Fabricate COSA Wafers (Hrs)			145.5	
Total Time to Bond All Wafers (Hrs)			2	
Total Time to Bake Bonded Wafers (Hrs)			24	
Estimated Total Time for Electronics wafer assembly			36	
Total Time for COSA Vehicle Manufacturing (Hrs)			207.5	

The LMES and the JLAB FEL can Serve as a Manufacturing Testbed for a High Throughput Patterning of Glass Ceramic Nanosatellite/COSA Parts

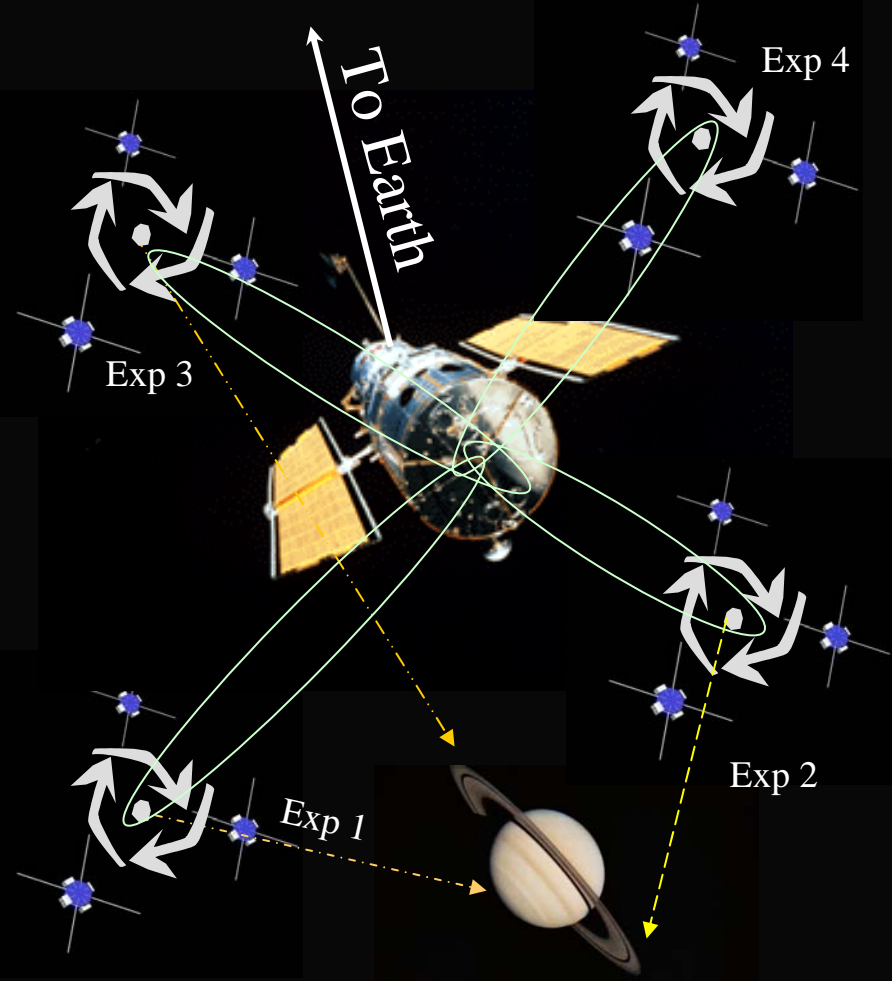
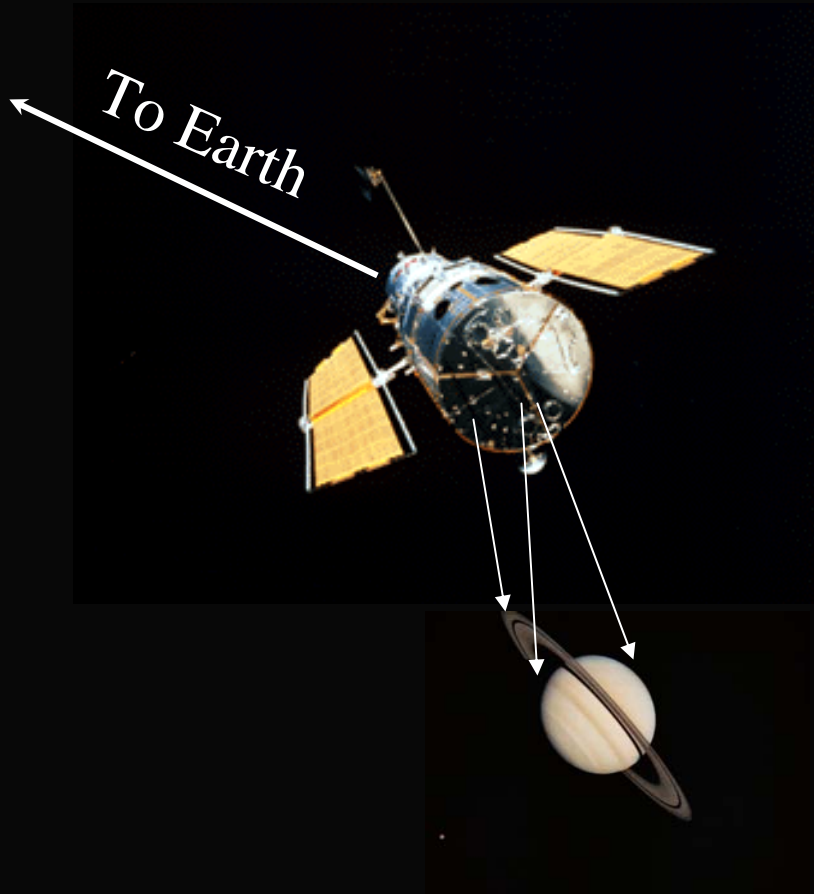
- A complete set of COSA vehicle wafers can be patterned in less than 30 minutes (instead of 55 hours).
- Multiple COSA vehicles can be assembled in batch mode in less than 30 hours (instead of 1 per 210 hrs).
- All digital direct manufacturing allows for design alterations to be done on the digital model of the vehicle which is directly realized in the processed part.

Changing the Approach on Future Space Missions

Adaptable Data Acquisition: Inspired by 3rd Generation (3G) Cell Phone Technology

Current Architecture Design
One Spacecraft

Future Architecture Design
“Mother & Daughter” Spacecraft



Conclusions

- Laser material processing is a growing industry world wide.
- Laser microengineering with the JLAB FEL can make high fidelity precision processes (e.g non thermally governed processes) commercially feasible for industrial use.
- A unique laser direct-write patterning tool (LMES) has been developed and installed at JLAB that permits the high fidelity controlled delivery of laser pulses based on a preprogrammed “script”.
- Laser microengineering becomes most cost effective when the laser is used only to “activate” the material not to induce the desired physical transformation process.
- The JLAB FEL with LMES patterning tool is a test bed for the manufacturing of miniature glass/ceramic space systems by a Direct-Digital Development methodology. “radically alter small satellite design and manufacture paradigms” – producing a nanosatellite space vehicle a day.



Thank You